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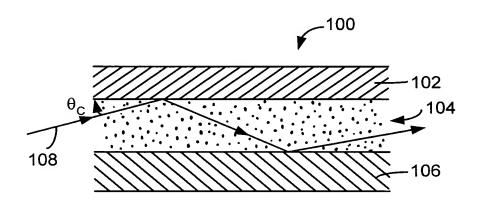


FIG. 1A

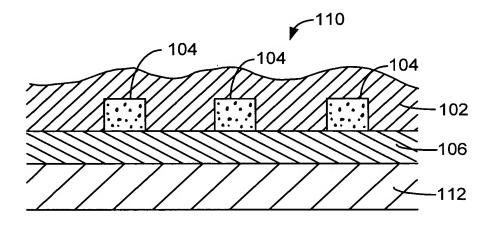
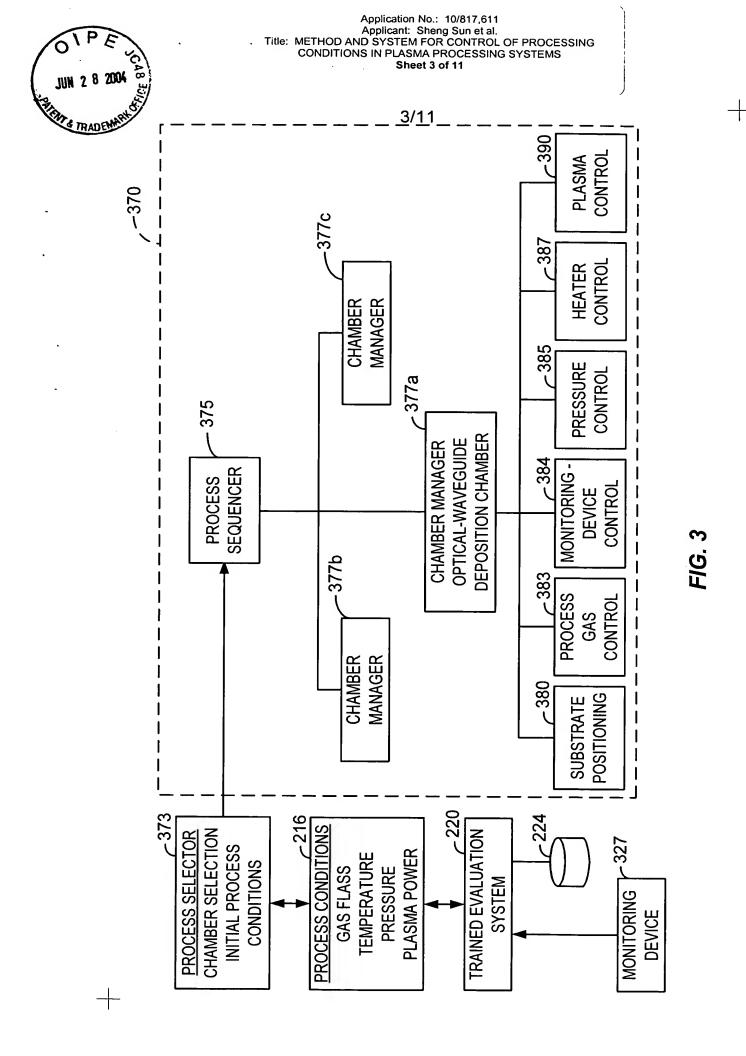


FIG. 1B

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JUN 2 8 2004 8 2004 PE JUN 2 8 2004 BE SEED TO THE TRADE MANUEL SEED TO

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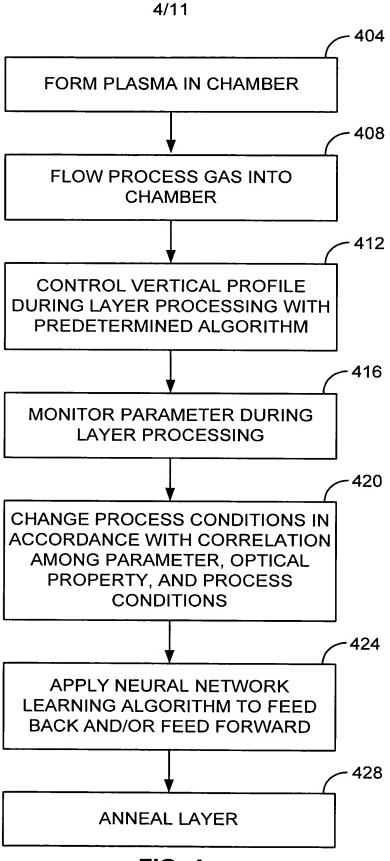


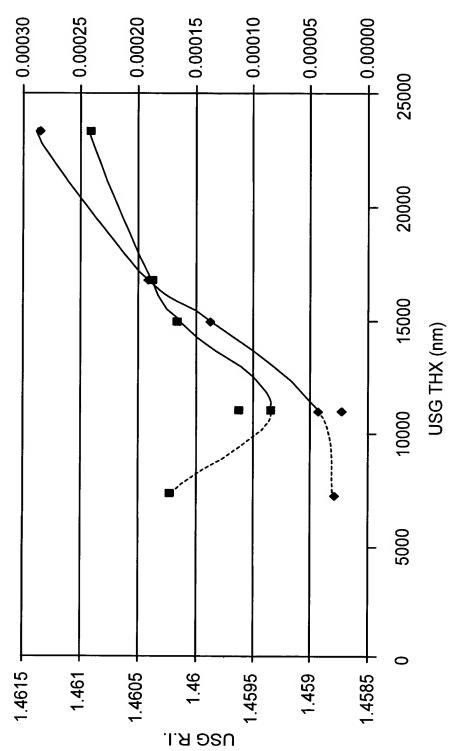
FIG. 4

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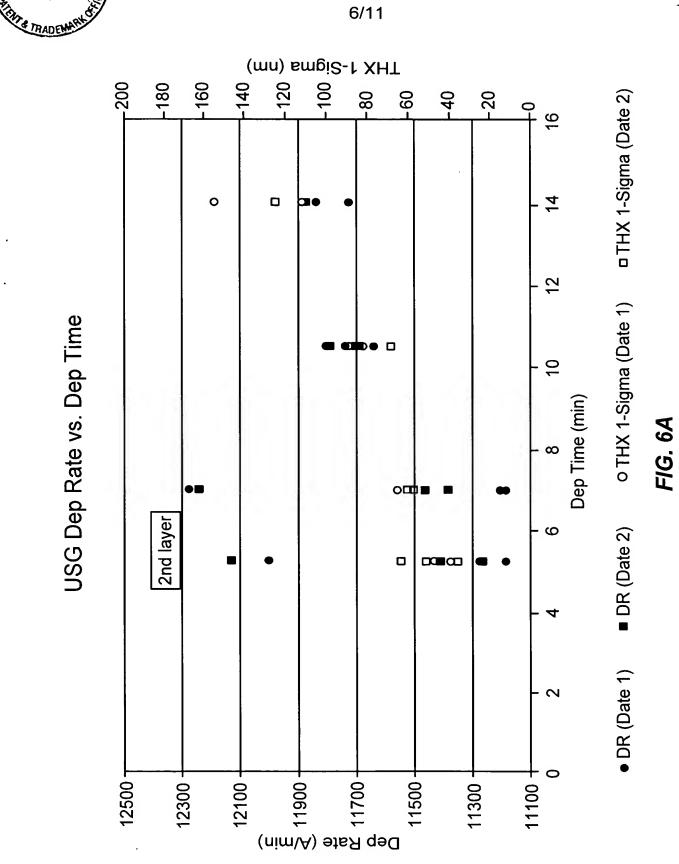
USG R.I. vs. USG Film THX

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F/G. 5

→ Avg R.I. → R.I. 1-Sigma



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USG R.I. vs. Dep Time



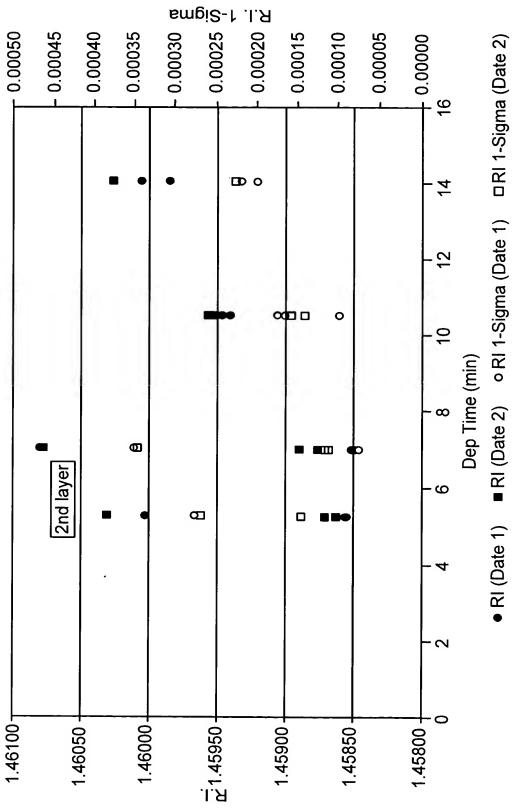
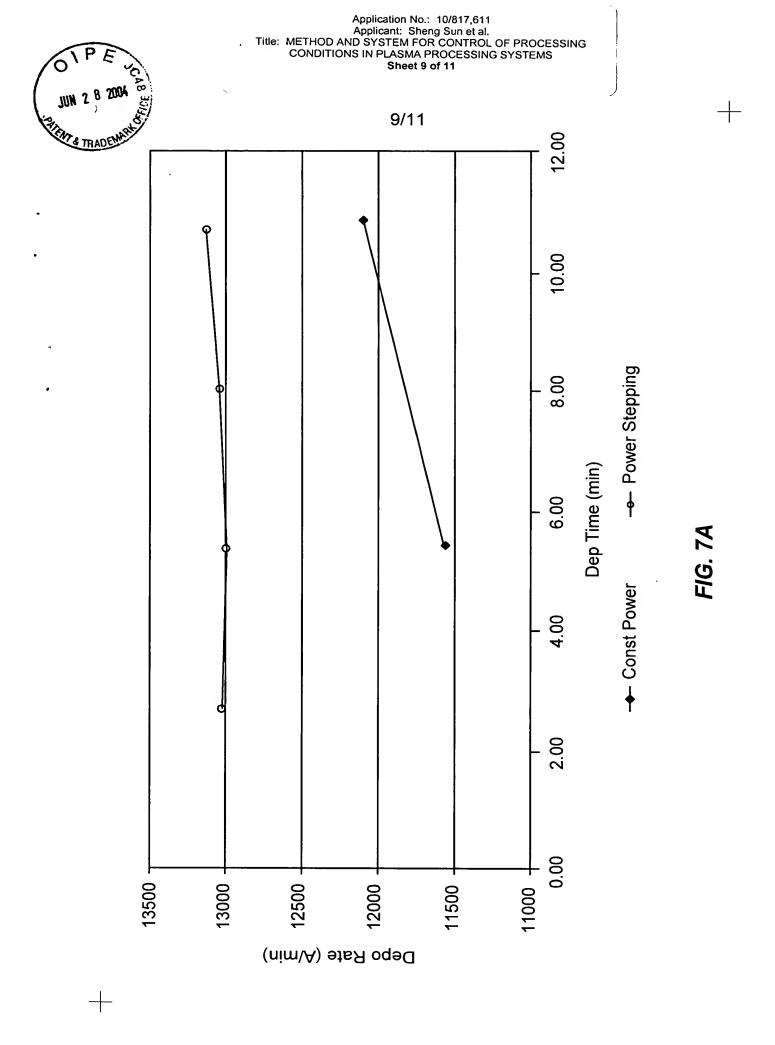


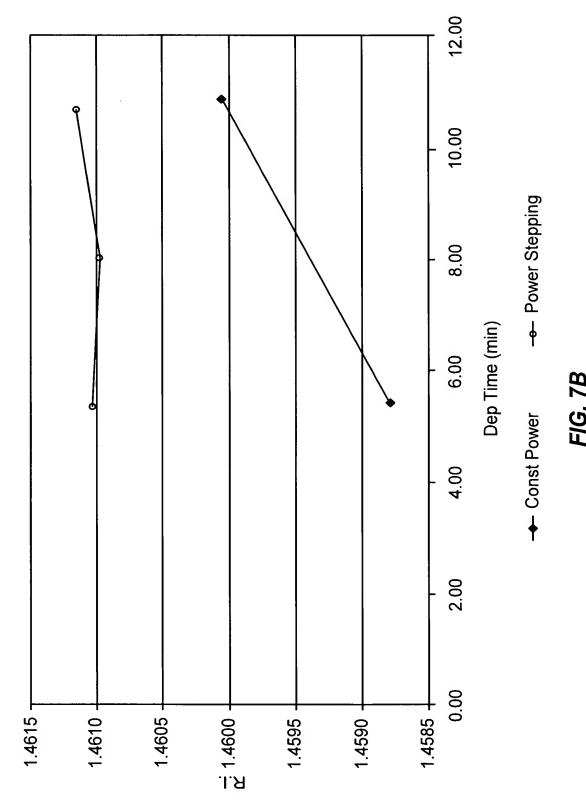
FIG. 6B





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